

Supporting Information

for

Low temperature atomic layer deposition of cobalt using dicobalt hexacarbonyl-1-heptyne as precursor

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Additional figures with XPS and ellipsometry raw data

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Preliminary Experiments in CVD mode



Figure S1: XPS overview spectrum of CVD film deposited at 150 °C and the relevant elemental binding energies and Auger transitions for the measured elements.



Figure S2: XPS measurements of CVD film deposited at 150 °C. The peaks for the O 1s and C 1s transitions were fitted with just one Voigt curve per main feature.

ALD with [Co₂(CO)₆HC≡CC₅H₁₁] and H₂ plasma



Figure S3: XPS overview spectrum of ALD film deposited at 35 °C and the relevant elemental binding energies and Auger transitions for the measured elements.



Figure S4: XPS overview spectrum of ALD film deposited at 85 °C and the relevant elemental binding energies and Auger transitions for the measured elements.



Figure S5: Ellipsometry raw data for ALD at 85 °C on 100 nm SiO₂.